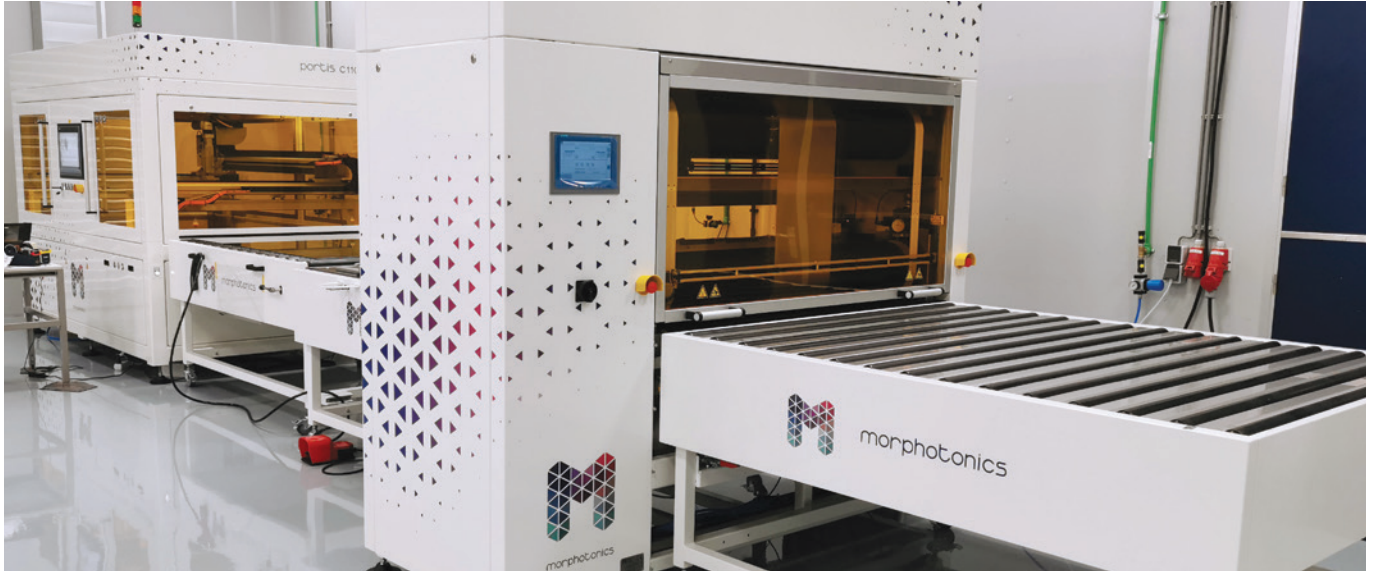


# Portis 1100 Platform

World's largest area nanoimprinting equipment



Portis 1100 is a modular Roll-to-Plate (R2P) nanoimprint equipment designed for R&D, process development, and production, with large-area capability. Portis 1100 offers a configurable and expendable nanoimprinting platform, combining Primer (P1100), Coater (C1100) and Imprint (NIL1100) modules.

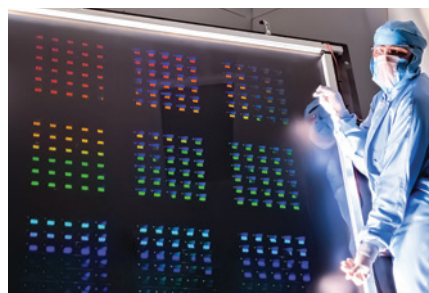
The Portis 1100 platform enables the production of substrates for diverse applications that demand thin residual layer thicknesses, air-exclusion during imprinting with high-viscosity materials, and high lateral dimension stability. It is designed to satisfy the R&D and production requirements of clients by offering compatibility with a range of pre-treatment and post-processing alternatives.

Substrate Size	Up to Gen5 (1100 x 1300 mm <sup>2</sup> )
Substrate Thickness	0.5 – 10 mm
Substrate materials	Rigid & flexible (glass, polymer, metal)
Structures	From 50 nm up to 500 µm
TAKT time	<5 min possible
Wide viscosity range (5-1500 mPas) using Coater C1100	
Programmable & accurate spray coating using Primer P1100	

The modules operate entirely automatically for their respective processes, while substrate loading and unloading, as well as module transportation, are carried out manually. With the use of standalone modules, the setup allows for flexibility to switch between different products and processes, and to add or modify modules as necessary in the future.



**Watch our Portis equipment in action**



**Any optics, any display, any size**

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Nanoimprint technologies